NANOFABRICATION FACILITY ADVANCED SCIENCE RESEARCH CENTER





ΕΓΙΟΙΙΧ

Using WecaS for Elionix EBL CAD File Conversion

And Considerations for Choosing Write Parameters

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Acknowledgements



Sky on Sky: https://vonoff.com/

ELIONIX 株式会社 エリオニクス





Electron Optics Column and Stage



Beam Deflector and Beam Blanker



Elionix Breaks the CAD into Fields



Fields – Subfields – Polygons and E-Beam Spots



- Each field is broken into 20 subfields
- Each subfield is broken into trapazoids
- Each trapazoid is filled by E-beam shots

Rastor Scanning

Raster scan

The beam is scanned over all surface area, while turning on/off the beam according to the presence or absence of a pattern





Factors Affecting the Beam Spot Size



Beam Spot Size for the 100keV Elionix



Beam Current	OLAP	Beam Diameter	
100pA	120um	1.8nm	
200pA	120um	2nm	
500pA	120um	2.1nm	
1nA	120um	2.3nm	
2nA	120um	3nm	
5nA	120um	5nm	
10nA	120um	10nm	
10nA	240um	15nm	
20nA	240um	25nm	
50nA	240um	90nm	
100nA	240um	300nm	

Beam Spot Size for the 50keV Elionix



Step 1. Choose the Beam Current and Aperture



- How small you need to go depends on your minimum feature size
- Larger beam currents mean shorter write times

Step 2. Choose a Field Size

1500µm



Maximum Field Sizes:

- 100keV = 1000 μm
- 50keV = 1500 μm

Field size can be critical – more to follow

Step 3. Define CAD Grid (Dot Number)

Beam Position Resolution = Field Size / Dot Number

0.01 um (500/50000)



(50,000 dots division)

		Dot Number			
		50,000	200,000	500,000	1,000,000
	100um	2nm	0.5nm	0.2nm	0.1nm
Field Size	250um	5nm	1.25nm	0.5nm	0.25nm
	500um	10nm	2.5nm	1nm	0.5nm
	1000um	20nm	5nm	2nm	1nm

Step 4. Choose Scan and Feed Pitch



Considerations: Feature Size

Shot pitch=6nm line width=10nm



Examples with different shot pitch





How a shape is written with E-Beam



"Pitch 1" = 1, "Pitch 2" = 1 (All-points Irradiation)



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"Pitch 1" = 2, "Pitch 2" = 1 (Scan every other one)
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- O Dots that beams are irradiated to
- O Dots that beams are not irradiated to

Issue: Stitching Errors at Field Boundaries



Writing field

Stitching Accuracy: ~ 15-20 nm



Field Correction for Dynamic Focus Correction



Fig. 1. Types of field stitching errors: (a) ideal case $|\Delta \mathbf{r}| = F_x$; (b) shift error, $|\Delta \mathbf{r}| \neq F_x$, $\Delta \mathbf{r}' = \Delta \mathbf{r} + \delta \mathbf{r}$; (c) field distortion, $\mathbf{S}' = \mathbf{S} + [\delta \mathbf{s}_{ij}]$; (d) field rotation, $\delta \mathbf{r}_{sot} = ((y - y_0)\delta\phi, (x_0 - x)\delta\phi)$; (e) deflector scale error, $F_x' \neq F_x$; (f) combined error, $3\sigma = 20-100$ nm.

Choosing Best Field Size and Placement



Electron Scattering in the resist helps - PSF



Charging Issues



Charging Issues



front side Au





Proximity Effect Issues



Proximity Effect solution: Dose Modulation -- Beamer





Proximity Effect (Solved)





Im

0.737

Resists and Exposure Doses (μ C/cm²)

Some common E-Beam resists

- PMMA Positive E-beam / DUV Resist (ASRC)
- Ma-N Negative DUV / E-beam Resist (ASRC)
- SU-8 Negative DUV resist
- HSQ (Hydrogen Silsesquioxane) Negative "Spin-on-glass" (USER)
- ZEP Positive Resist (USER but could be purchased through the ASRC)

Anti-Charging Agents for Insulating Substrates

- Espacer (User owned)
- DisCharge (DisChem Inc) (User owned)
- Gold Sputter Tool (inside cleanroom)

WecaS



Data structure / Files created





WecaS

- 1) Calculate the dose time (μ s/dot)
- 2) Define CAD Grid (Field, Dots)
- 3) GDS/DXF Conversion \rightarrow into CELL file
- 4) Set Pitch/Dose
- 5) Place / Compute Fields
- 6) Save CON File
- 7) Edit Schedule Execution
 - a. Dose Assignment
 - b. Set Options



(1) Estimate Dose



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- Depends on Resist, Developer, Vacc, etc.
- Calculate Dose Time [usec]
 - Decide Field Size, #Dot, Beam Current.

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.CON

Open

CON

Open

.CEL

Dose

Calculator (

- Min; 0.01 usec
- Max; 1300 usec

File(F) Parameters(P) View(V) Tool(T) Maintenance(M) Help(H)

WECAS for ELS-G100 (100[micron2],1000000[dot]

10

DXF

File

Select Field

Size/Dot



Edit Schedule

Execution >

Input Unit

mm

(2) Define the Field Size and the Grid

WECAS for ELS-G100 (100[micron2],1000000[dot])				- 🗆 🗙
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(3) Convert GDSII/DXF into Cell File

WECAS for ELS-G100 (100[micron2],1000000[dot])		
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Note: Writing / CAD Area – 1st Quadrant Only



(4) Set Pitch and Dose

WECAS for ELS-G100 (100[micron2],1000	0000[dot])	
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(5) Auto Placement of Fields



(6) Save .SCON File



(7a) Create Schedule File – Dose Assignment



(7b) Schedule File – Set Option and Preset Height

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Sample Holder Change(C) Clear(L) XY-Laser REAL TIME Z-Movement Mode PRESET(HS ON) Z Preset [mm] 3.2 Z Tolerance [um] 0.5 HS Error Process © Cont. © Abort	Registration Global Mark (Reg-2) Image: OFF Image: OFF <th>Local Mark (Reg-4) © OFF ON Search Settings & View Profile Dynamic Correction OFF ON Scan Type Oigital Analog</th> <th>Periodic Correction OFF ON Mode POS Timer 20 [min] Dose Correction OFF ON Target Beam Current Set By Input Input Use Input Value 1.0e-9 [A] Wide Area Correction OFF ON Wide Area Correction</th> <th>Width Modulation OFF ON Equation a * mod + b (X) Equation Param - a 1 (X) Equation Param - b 0 (Y) Equation Param - a 0.975 (Y) Equation Param - b 0 Dose Time Interpolation © OFF ON Dose Blanking © OFF ON</th>	Local Mark (Reg-4) © OFF ON Search Settings & View Profile Dynamic Correction OFF ON Scan Type Oigital Analog	Periodic Correction OFF ON Mode POS Timer 20 [min] Dose Correction OFF ON Target Beam Current Set By Input Input Use Input Value 1.0e-9 [A] Wide Area Correction OFF ON Wide Area Correction	Width Modulation OFF ON Equation a * mod + b (X) Equation Param - a 1 (X) Equation Param - b 0 (Y) Equation Param - a 0.975 (Y) Equation Param - b 0 Dose Time Interpolation © OFF ON Dose Blanking © OFF ON
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Preset Height and Height Sensor



Stage

Preset Height and Height Sensor



Stage

Preset Height (offset)





CAD Conversion ONLY on CAD-PCs (!)



- Start the conversion process by creating a directory for this job
- Save entire folder on the CAD-PC (.cel, .sccc, .scbc, .scon, .sc8)
- Will transfer folder to the "Online PC" when at the tool
- Estimate your write time before reserving the tool!

Elionix Reservation Policies

- 10 Day Reservation Horizon for each tool
- No more than 3 reservations at a time
- No more than 1 prime time reservation at a time
- Number of reservations limited NOT hours
- Reserve only the time that you need

Cancelation Policies

- Must cancel at least 24 hours before beginning of the reservation
- If reservation efficiency is below 80% you will receive warning Thereafter will either be charged or loose reservation access or both



